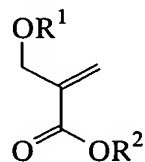


ABSTRACT

Alicyclic methacrylate compounds having an oxygen
5 substituent group on their α -methyl group, represented by
formula (1), are novel wherein R^1 is H or C_1 - C_{10} alkyl which
may contain a halogen atom, hydroxyl group, ether bond,
carbonyl group, carboxyl group or cyano group, and R^2 is a
monovalent C_3 - C_{20} organic group having an alicyclic structure.
10 Polymers prepared from these alicyclic methacrylate compounds
have improved transparency, especially at the exposure
wavelength of an excimer laser, and improved dry etching
resistance. Resist compositions comprising the polymers are
sensitive to high-energy radiation, show a high resolution,
15 allow smooth development, lend themselves to micropatterning,
and are thus suitable as micropatterning material for VLSI
fabrication.



(1)